EUV Mask Microscope for Lithography Generations

Customer:
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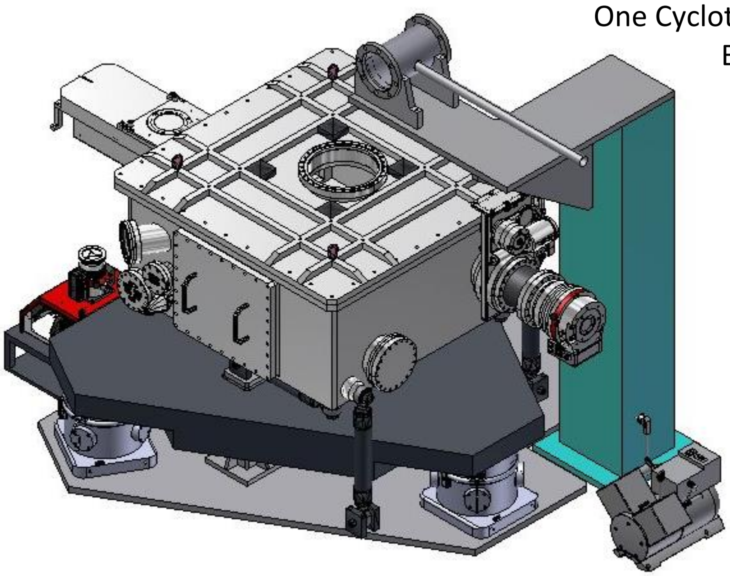

ADC designed, built and installed SHARP (the SEMATECH High-NA Actinic Reticle review Project) an actinic, synchrotron-based microscope dedicated to extreme ultraviolet (EUV) photomask research for Lawrence Berkeley National Laboratory. The system demonstrated the addition of complementary imaging modes to the SHARP EUV mask microscope, in an effort to extract additional information from actinic photomask imaging, improve navigation and enhance defect detection.